## Contents

1	Introduction. Theory and Experiment of High-Order Harmonic				
	Gen	eration in Narrow and Extended Media	1		
	1.1	High-Order Harmonic Generation in Isotropic Medium: Three-Step Model and Macroscopic Consideration of Frequency			
	1.2	Conversion	1		
		for the HHG	4		
	Refe	erences	6		
2	HH	G in Short-Length Plasmas	9		
	2.1	Modern History and Perspectives of Harmonic Generation			
		in Narrow Plasma Plumes	9		
	2.2	Spatial Coherence Measurements of Non-resonant			
		and Resonant High-Order Harmonics Generated in Narrow			
		Laser Ablation Plumes	14		
	2.3	Resonance Processes in the Plasma Plumes	21		
		2.3.1 Resonant and Non-resonant High-Order Harmonic			
		Generation in the Plasmas Produced by Picosecond			
		and Femtosecond Pulses.	21		
		2.3.2 Resonance Enhancement of the 11th Harmonic			
		of 1064 nm Picosecond Radiation Generated	•		
		in Lead Plasma	28		
	2.4	Peculiarities of the High-Order Harmonics from Different			
		Narrow Plasmas Generating at 1 kHz Repetition Rate	37		
	2.5	Concluding Comments	45		
	Refe	erences	46		
3	HH	G in Extended Plasmas	51		
	3.1	Advanced Properties of Extended Plasmas for Efficient			
		High-Order Harmonic Generation	51		

Contents

	3.2	Enhanced Harmonic Generation Using Different Second-Harmonic Sources for the Two-Color	
		Pump of Extended Laser-Produced Plasmas	57
	3.3	Modification of Modulated Plasma Plumes	67
	3.4	Characterization of the High-Order Harmonics	07
	5.4	of 64 fs Pulses Generated in Extended Plasma Plumes	73
	3.5	Concluding Comments	80
		rences	81
4		si-Phase-Matching of Harmonics in Laser-Produced	85
	<b>4</b> .1	mas Perforated Target Ablation for the Formation	05
	4.1	of the Modulated Plasma for Quasi-Phase-Matched	
		Harmonic Generation	87
	4.2	Quasi-Phase-Matching of Harmonics Using the Variable	07
	4.2	Multi-jet Plasmas.	92
	4.3	QPM-Induced Enhancement of HHG During Two-Color Pump	92
	4.5	of Multi-jet Plasmas	98
	4.4	Peculiarities of QPM Harmonics Using Different Targets	70
	4.4	and Pump Schemes	103
	4.5	Influence of Plasma Jet Sizes and Pulse Energies	105
	4.5	on the Characteristics of QPM Harmonics.	108
	4.6	Concluding Comments	116
		6	
	Refe	rences	117
_		rences	117
5	Pecu	liarities of the HHG in the Extended Plasmas Produced	
5	Pecu on t	liarities of the HHG in the Extended Plasmas Produced ne Surfaces of Different Materials	117 119
5	Pecu	Iliarities of the HHG in the Extended Plasmas Produced ne Surfaces of Different Materials	119
5	Pecu on the state of the state	liarities of the HHG in the Extended Plasmas Produced ne Surfaces of Different Materials	
5	Pecu on t	liarities of the HHG in the Extended Plasmas Produced he Surfaces of Different Materials Harmonic Generation in the Plasmas Produced on the 5-mm-Long Crystal Surfaces Application of the Laser Plasmas Produced	119 121
5	Pecu on tl 5.1 5.2	Iliarities of the HHG in the Extended Plasmas Producedhe Surfaces of Different MaterialsHarmonic Generation in the Plasmas Producedon the 5-mm-Long Crystal SurfacesApplication of the Laser Plasmas Producedon the Extended Surfaces of Elemental Semiconductors	119
5	Pecu on the state of the state	Iliarities of the HHG in the Extended Plasmas Producedhe Surfaces of Different Materials.Harmonic Generation in the Plasmas Producedon the 5-mm-Long Crystal Surfaces.Application of the Laser Plasmas Producedon the Extended Surfaces of Elemental SemiconductorsApplication of Carbon Cluster-Contained Extended Plasmas	119 121 127
5	Pecu on tl 5.1 5.2 5.3	liarities of the HHG in the Extended Plasmas Produced ne Surfaces of Different Materials	119 121
5	Pecu on tl 5.1 5.2	liarities of the HHG in the Extended Plasmas Produced he Surfaces of Different Materials	119 121 127
5	Pecu on tl 5.1 5.2 5.3	Iliarities of the HHG in the Extended Plasmas Producedhe Surfaces of Different Materials.Harmonic Generation in the Plasmas Producedon the 5-mm-Long Crystal Surfaces.Application of the Laser Plasmas Producedon the Extended Surfaces of Elemental SemiconductorsApplication of Carbon Cluster-Contained Extended Plasmasfor the High-Order Harmonic Generation of Ultrashort PulsesMorphology of Laser-Produced Carbon Nanoparticle Plasmasand High-Order Harmonic Generation of Ultrashort Pulses	<ol> <li>119</li> <li>121</li> <li>127</li> <li>133</li> </ol>
5	Pecu on th 5.1 5.2 5.3 5.4	Iliarities of the HHG in the Extended Plasmas Producedhe Surfaces of Different Materials.Harmonic Generation in the Plasmas Producedon the 5-mm-Long Crystal SurfacesApplication of the Laser Plasmas Producedon the Extended Surfaces of Elemental SemiconductorsApplication of Carbon Cluster-Contained Extended Plasmasfor the High-Order Harmonic Generation of Ultrashort PulsesMorphology of Laser-Produced Carbon Nanoparticle Plasmasand High-Order Harmonic Generation of Ultrashort Pulsesin Extended Clustered Media	119 121 127
5	Pecu on tl 5.1 5.2 5.3	Iliarities of the HHG in the Extended Plasmas Producedhe Surfaces of Different Materials.Harmonic Generation in the Plasmas Producedon the 5-mm-Long Crystal Surfaces.Application of the Laser Plasmas Producedon the Extended Surfaces of Elemental SemiconductorsApplication of Carbon Cluster-Contained Extended Plasmasfor the High-Order Harmonic Generation of Ultrashort PulsesMorphology of Laser-Produced Carbon Nanoparticle Plasmasand High-Order Harmonic Generation of Ultrashort Pulsesin Extended Clustered MediaGraphene-Contained Extended Plasma: A Medium	<ul><li>119</li><li>121</li><li>127</li><li>133</li><li>139</li></ul>
5	Pecu on tl 5.1 5.2 5.3 5.4 5.5	Iliarities of the HHG in the Extended Plasmas Producedhe Surfaces of Different Materials.Harmonic Generation in the Plasmas Producedon the 5-mm-Long Crystal Surfaces.Application of the Laser Plasmas Producedon the Extended Surfaces of Elemental SemiconductorsApplication of Carbon Cluster-Contained Extended Plasmasfor the High-Order Harmonic Generation of Ultrashort PulsesMorphology of Laser-Produced Carbon Nanoparticle Plasmasand High-Order Harmonic Generation of Ultrashort Pulsesin Extended Clustered MediaGraphene-Contained Extended Plasma: A Mediumfor the Coherent Extreme Ultraviolet Light Generation	<ul> <li>119</li> <li>121</li> <li>127</li> <li>133</li> <li>139</li> <li>150</li> </ul>
5	Pecu on th 5.1 5.2 5.3 5.4 5.5 5.6	Iliarities of the HHG in the Extended Plasmas Producedhe Surfaces of Different Materials.Harmonic Generation in the Plasmas Producedon the 5-mm-Long Crystal SurfacesApplication of the Laser Plasmas Producedon the Extended Surfaces of Elemental SemiconductorsApplication of Carbon Cluster-Contained Extended Plasmasfor the High-Order Harmonic Generation of Ultrashort PulsesMorphology of Laser-Produced Carbon Nanoparticle Plasmasand High-Order Harmonic Generation of Ultrashort Pulsesin Extended Clustered MediaGraphene-Contained Extended Plasma: A Mediumfor the Coherent Extreme Ultraviolet Light GenerationConcluding Comments	<ul> <li>119</li> <li>121</li> <li>127</li> <li>133</li> <li>139</li> <li>150</li> <li>153</li> </ul>
5	Pecu on th 5.1 5.2 5.3 5.4 5.5 5.6	Iliarities of the HHG in the Extended Plasmas Producedhe Surfaces of Different Materials.Harmonic Generation in the Plasmas Producedon the 5-mm-Long Crystal Surfaces.Application of the Laser Plasmas Producedon the Extended Surfaces of Elemental SemiconductorsApplication of Carbon Cluster-Contained Extended Plasmasfor the High-Order Harmonic Generation of Ultrashort PulsesMorphology of Laser-Produced Carbon Nanoparticle Plasmasand High-Order Harmonic Generation of Ultrashort Pulsesin Extended Clustered MediaGraphene-Contained Extended Plasma: A Mediumfor the Coherent Extreme Ultraviolet Light Generation	<ul> <li>119</li> <li>121</li> <li>127</li> <li>133</li> <li>139</li> <li>150</li> </ul>
5	Pecu on th 5.1 5.2 5.3 5.4 5.5 5.6 Refe New	Iliarities of the HHG in the Extended Plasmas Produced         he Surfaces of Different Materials.         Harmonic Generation in the Plasmas Produced         on the 5-mm-Long Crystal Surfaces.         Application of the Laser Plasmas Produced         on the Extended Surfaces of Elemental Semiconductors         Application of Carbon Cluster-Contained Extended Plasmas         for the High-Order Harmonic Generation of Ultrashort Pulses         Morphology of Laser-Produced Carbon Nanoparticle Plasmas         and High-Order Harmonic Generation of Ultrashort Pulses         in Extended Clustered Media         Graphene-Contained Extended Plasma: A Medium         for the Coherent Extreme Ultraviolet Light Generation         concluding Comments         rences	<ul> <li>119</li> <li>121</li> <li>127</li> <li>133</li> <li>139</li> <li>150</li> <li>153</li> <li>155</li> </ul>
_	Pecu on tl 5.1 5.2 5.3 5.4 5.5 5.6 Refe New Gen	Iliarities of the HHG in the Extended Plasmas Produced         he Surfaces of Different Materials.         Harmonic Generation in the Plasmas Produced         on the 5-mm-Long Crystal Surfaces.         Application of the Laser Plasmas Produced         on the Extended Surfaces of Elemental Semiconductors         Application of Carbon Cluster-Contained Extended Plasmas         for the High-Order Harmonic Generation of Ultrashort Pulses         Morphology of Laser-Produced Carbon Nanoparticle Plasmas         and High-Order Harmonic Generation of Ultrashort Pulses         in Extended Clustered Media         Graphene-Contained Extended Plasma: A Medium         for the Coherent Extreme Ultraviolet Light Generation         concluding Comments         rences	<ul> <li>119</li> <li>121</li> <li>127</li> <li>133</li> <li>139</li> <li>150</li> <li>153</li> </ul>
_	Pecu on th 5.1 5.2 5.3 5.4 5.5 5.6 Refe New	Iliarities of the HHG in the Extended Plasmas Produced         he Surfaces of Different Materials.         Harmonic Generation in the Plasmas Produced         on the 5-mm-Long Crystal Surfaces         Application of the Laser Plasmas Produced         on the Extended Surfaces of Elemental Semiconductors         Application of Carbon Cluster-Contained Extended Plasmas         for the High-Order Harmonic Generation of Ultrashort Pulses         Morphology of Laser-Produced Carbon Nanoparticle Plasmas         and High-Order Harmonic Generation of Ultrashort Pulses         in Extended Clustered Media         Graphene-Contained Extended Plasma: A Medium         for the Coherent Extreme Ultraviolet Light Generation         concluding Comments         rences         Third and Fourth Harmonics Generation in Laser-Induced	<ol> <li>119</li> <li>121</li> <li>127</li> <li>133</li> <li>139</li> <li>150</li> <li>153</li> <li>155</li> <li>161</li> </ol>
_	Pecu on tl 5.1 5.2 5.3 5.4 5.5 5.6 Refe New Gen	Iliarities of the HHG in the Extended Plasmas Produced         he Surfaces of Different Materials.         Harmonic Generation in the Plasmas Produced         on the 5-mm-Long Crystal Surfaces.         Application of the Laser Plasmas Produced         on the Extended Surfaces of Elemental Semiconductors         Application of Carbon Cluster-Contained Extended Plasmas         for the High-Order Harmonic Generation of Ultrashort Pulses         Morphology of Laser-Produced Carbon Nanoparticle Plasmas         and High-Order Harmonic Generation of Ultrashort Pulses         in Extended Clustered Media         Graphene-Contained Extended Plasma: A Medium         for the Coherent Extreme Ultraviolet Light Generation         concluding Comments         rences	<ul> <li>119</li> <li>121</li> <li>127</li> <li>133</li> <li>139</li> <li>150</li> <li>153</li> <li>155</li> </ul>

	6.2	Resonance-Enhanced Harmonics Generated in Nanoparticle			
	0.2	and Monomer Plasmas	170		
	6.3	Electron Density Measurements in Laser-Produced Plasma			
		Using the Nonlinear Optical Method	178		
	6.4	Concluding Comments	185		
	Refe	rences	187		
7	Harmonic Characterization Using Different HHG Schemes				
	in th	e Extended Plasmas	189		
	7.1	Low- and High-Order Harmonic Generation in the Extended			
		Plasmas Produced by Laser Ablation of Zinc and Manganese			
		Targets	190		
	7.2	Application of Double Femtosecond Pulses for Plasma			
		Harmonic Generation	200		
	7.3	Concluding Comments	207		
	Refe	erences	207		
8	Summary: Achievements and Perspectives				
	Refe	erences	216		
-			219		
In	( <b>ndex</b>				

xiii